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	Application No.	Applicant(s)	•
Notice of Allowability	10/087,735	NAGAI ET AL.	
	Examiner	Art Unit	
	John S. Chu	1752	
The MAILING DATE of this communication appear All claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) of NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGOR (The Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in thi or other appropriate communic GHTS. This application is subi	is application. If not included	se. THIS he initiative
1. \boxtimes This communication is responsive to $7/21/04$.			
2. The allowed claim(s) is/are 2-23.			
3. The drawings filed on are accepted by the Examiner			
4. Acknowledgment is made of a claim for foreign priority under a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMETHIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submitted in the submit in th	been received. been received in Application N cuments have been received in of this communication to file a re ENT of this application.	this national stage application freeply complying with the requiren	nents
 CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftsperso 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the 	on's Patent Drawing Review (FAME) Amendment / Comment or in the displayed on the displayed be written on the displayed by the displayed on the displayed by th	the Office action of	<u>;</u>) of
DEPOSIT OF and/or INFORMATION about the depos attached Examiner's comment regarding REQUIREMENT F	it of BIOLOGICAL MATERIA	AL must be submitted. Note the	he
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summ Paper No./Mail 3), 7. ⊠ Examiner's Ame	I Date	

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EXAMINER'S AMENDMENT/REASONS FOR ALLOWANCE

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Chris Raimond on August 31, 2004.

The application has been amended as follows:

Claim 21, line 2 insert the following formula --

$$R^{1} - C - C - O - R^{3}$$

$$N$$

$$(1)$$

This insertion reinserts the formula inadvertently omitted from the claims in the amendment submitted August 25, 2004.

REASONS FOR ALLOWANCE

2. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following:

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2. Previously Presented) A carbazole derivative of the following formula (1),

wherein R¹ and R² in the formula (1) independently represent a linear, branched, or cyclic alkyl group having 1-12 carbon atoms, an aromatic hydrocarbon group having 6-20 carbon atoms, an oxygen-containing organic group, or a nitrogen-containing organic group, and wherein R³ represents a hydrogen atom or a monovalent organic group.

6. (Currently Amended) A carbazole derivative of the following formula (1),

$$\begin{array}{c|c} R^2 & O \\ \hline \\ R^1 & C & C & O & R^3 \end{array}$$

wherein R¹ and R² individually represent a hydrogen atom or a monovalent organic group, or R¹ and R² form, together with the carbon atom to which R¹ and R² bond, a divalent organic group having a 3-8 member carbocyclic structure or a 3-8 member heterocyclic structure, and wherein R³ in the formula (1) is an i-propyl group, t-butyl group, or a cyclohexyl group[[,]] or benzyl-group.

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21. (New) a carbazole derivative of the following formula (1),

wherein R¹ represents a hydrogen atom or a monovalent organic group and R² represents a monovalent organic group, or R¹ and R² form, together with the carbon atom to which R¹ and R² bond, a divalent organic group having a 3-8 member carbocyclic structure or a 3-8 member heterocyclic structure with the proviso that when R¹ represents a hydrogen atom, R² is selected from the group consisting of an ethyl group, an n-propyl group, an i-propyl group, an n-butyl group, a 2-methylpropyl group, a 1-methylpropyl group, a t-butyl group, a phenyl group, and a benzyl group, and wherein R³ in the formula (1) is an i-propyl group, t-butyl group, cyclohexyl group, or benzyl group.

10. (Previous) Presented) A positive tone radiation-sensitive resin composition comprising (A) a carbazole derivative of the following formula (1),

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b

$$R^{1} - \stackrel{\stackrel{\scriptstyle \bullet}{\downarrow}}{\downarrow} - \stackrel{\scriptstyle \bullet}{\downarrow} - \circ - R^{3}$$

wherein R¹ and R² individually represent a hydrogen atom or a monovalent organic group, or R¹ and R² form, together with the carbon atom to which R¹ and R² bond, a divalent organic group having a 3-8 member carbocyclic structure or a 3-8 member heterocyclic structure, and R³ represents a hydrogen atom or a monovalent organic group, (B) an acid-dissociable groupcontaining resin which is insoluble or scarcely soluble in alkali, but becomes alkali soluble when the acid-dissociable group dissociates, and (C) a photoacid generator.

The claimed invention is to the particularly claimed carbazole compound and its presence in a chemically amplified radiation sensitive resin composition and in a positive tone radiation-sensitive resin composition. The closest prior art reference of record is to Shukla, Y.K. "Synthesis Of Some New Aryl α -(3)Substituted-Carbazol-9-YL) Acetates/Propionates As Possible Anti-inflammatory And Analgesic Agents", Indian J. Chem., 33B:799-802 (1994) (SHUKLA), wherein a carbazole compound is disclosed. Applicants have amended the claims to the carbazole compound by removing the limitation that R^3 is no longer a benzyl group. The claims are further drawn to a chemically amplified radiation sensitive resin composition and a positive tone radiation sensitive composition comprising said carbazole compound.

Further none of the prior art references disclose or suggest the particularly claimed carbazole compound or its presence in a chemically amplified radiation sensitive composition or

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in a positive tone radiation sensitive composition used for microfabrication of integrated circuit devices.

Because none of the prior art references disclose the claimed invention to the carbazole compound or the radiation sensitive resin compositions, claims 2-23 are seen as allowable and passed to issue.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

The fax phone number for the USPTO is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (571) 272-1700.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PMR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

John S. Chu

Primary Examiner, Group 1700

J.Chu August 31, 2004